

discloses polishing of a substrate surface before a film is formed. Accordingly, Omika fails to disclose polishing a metal deposited in a pattern of an insulating film. It is also submitted that the above art fails to teach the steps of washing the polished surface of the metal formed in the pattern by ultrasonic washing and thereafter subjecting the surface to a physical washing.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our below listed address.

Respectfully submitted,

  
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